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TITLE: GASKET

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INVENTOR-INFORMATION:

NAME

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ABSTRACT:

PURPOSE: To prevent corrosion due to gallium and indium in a molecular beam

epitaxy apparatus by coating a surface of a copper gasket with tantalum.

1. A gasket for a molecular beam epitaxy apparatus.

CONSTITUTION: A coating film 2 of tantalum, titanium, tungsten, molybdenum

or niobium is formed on a surface of a gasket 1 made of copper or silver or

*Needs to be mailed*

gold or aluminum. In applying the gasket 1 to a molecular beam epitaxy apparatus, any leak due to corrosion does not occur. Consequently, any equipment for replacing the gasket 1 is not necessary and a position for attaching a flange can be freely selected.

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